Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A sol ~~having a pH of 3 to 6 or 8 to 10 in which~~ comprising particles ~~are~~ dispersed in a medium, wherein:

~~the particles have a particle size of 50 to 150 nm, have a specific surface area of 2 to 200 m^2/g, and~~ the particles comprise as a main component crystalline cerium oxide of ~~the~~ cubic system and as an additional component a lanthanum compound, neodymium compound or a combination thereof~~, wherein~~;

the additional component is contained in an X/(Ce + X) molar ratio of 0.005 to 0.15 in which X is lanthanum atoms, neodymium atoms or a combination thereof;

the particles have a particle size of 50 to 150 nm;

the particles have a specific surface area of 2 to 200 m^2/g; and

the sol has a pH of 3 to 6 or 8 to 10.

2. (Original) A sol according to claim 1, wherein the additional component is a lanthanum compound.

3. (Original) A sol according to claim 1, wherein the additional component is a neodymium compound.

4-9. (Canceled)

10. (Currently Amended) An abrasive ~~containing~~ comprising a sol ~~having a pH of 3 to 6 or 8 to 10 in which~~ including particles ~~are~~ dispersed in an aqueous medium, wherein: ~~in a range of 0.1 to 50 wt%, wherein the particles have a particle size of 50 to 150 nm, have a specific surface area of 2 to 200 m^2/g, and~~

the particles comprise as a main component crystalline cerium oxide of ~~the~~ cubic system and as an additional component a lanthanum compound, neodymium compound or a combination thereof~~,~~; ~~wherein~~

the additional component is contained in an X/(Ce + X) molar ratio of 0.005 to 0.15 in which X is lanthanum atoms, neodymium atoms or a combination thereof;

the particles are present in the abrasive in an amount of 0.1 to 50 wt%;

the particles have a particle size of 50 to 150 nm;

the particles have a specific surface area of 2 to 200 m^2/g; and

the abrasive has a pH of 3 to 6 or 8 to 10.

11. (Canceled)

12. (Previously Presented) An abrasive according to claim 10, wherein the additional component is a lanthanum compound.

13. (Previously Presented) An abrasive according to claim 10, wherein the additional component is a neodymium compound.

14-15. (Canceled)

16. (Currently Amended) ~~An abrasive according to claim 10, which is used for~~ A method of polishing a substrate ~~which comprises~~ comprising silica as a main component, the method comprising applying the abrasive according to claim 10.

17. (Currently Amended) ~~An abrasive according to claim 10, which is used for~~ A method of polishing a rock crystal, a quartz glass for a photomask, a semiconductor device or a hard disk made of glass, the method comprising applying the abrasive according to claim 10.

18. (Currently Amended) ~~An abrasive according to claim 10, which is used in a step~~ A method of polishing an organic film, ~~a step of~~ polishing a Inter Layer Dielectric (ILD),

or conducting ~~or a step of~~ shallow trench isolation, ~~for polishing~~ to polish a semiconductor device, the method comprising applying the abrasive according to claim 10.